ABSTRACT

    This specification discloses an

exposure mask, a method of designing and

5 manufacturing an exposure mask, an exposure method

and apparatus, a pattern forming method, and a

device manufacturing method. Specifically, the

exposure mask is adapted to expose an image

forming layer provided on a substrate, by use of

10 near field light leaking from adjoining openings

formed in a light blocking member, wherein the

light blocking film has an opening interval that

is determined so that an electric field

distribution at the image forming layer side of

15 the opening to be defined as exposure light is

projected on the light blocking member has a

correlation with an eccentric model of electric

field distribution as determined by a linewidth

and a height of a pattern to be produced.

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